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(54) Title (EN): ARTIFICIAL GENOME MANIPULATION FOR GENE EXPRESSION REGULATION

(54) Title (FR): MANIPULATION ARTIFICIELLE DE GÉNOME POUR LA RÉGULATION D'EXPRESSION GÉNIQUE

(54) Title (KO): 유전자 발현 조절을 위한 인위적인 게놈 조작

(57) Abstract:

(EN): The present invention relates to an expression control composition for regulating the expression of repeated genes or a method using the same. More specifically, the present invention relates to a composition for expression regulation, comprising a guide nucleic acid capable of targeting a transcription regulatory region of repeated genes, and a method for regulating the expression of repeated genes, using the composition to artificially manipulate and/or modify a transcription regulatory region of the repeated genes. In addition, the present invention relates to a method for treating or alleviating a disease caused by gene repetition, using an expression control composition for regulating the expression of repeated genes.

(FR): La présente invention concerne une composition de contrôle d'expression pour réguler l'expression de gènes répétés ou un procédé l'utilisant. Plus spécifiquement, la présente invention concerne une composition pour la régulation d'expression, comprenant un acide nucléique de guidage capable de cibler une région régulatrice de transcription de gènes répétés, et un procédé de régulation de l'expression de gènes répétés, utilisant la composition pour manipuler et/ou modifier artificiellement une région régulatrice de transcription des gènes répétés. De plus, la présente invention concerne une méthode pour traiter ou soulager une maladie provoquée par la répétition de gènes, à l'aide d'une composition de contrôle d'expression pour réguler l'expression de gènes répétés.

(KO): 본 발명은 중복 유전자의 발현을 조절하기 위한 발현 조절용 조성물 또는 이를 이용한 방법에 관한 것이다. 보다 구체적으로, 중복 유전자의 전사 조절 영역을 표적화할 수 있는 가이드핵산을 포함하는 발현 조절용 조성물 및 이를 이용한 중복 유전자의 전사 조절 영역을 인위적으로 조작 및/또는 변형시켜 중복 유전자의 발현을 조절하는 방법에 관한 것이다. 또한 중복 유전자의 발현을 조절하기 위한 발현 조절용 조성물을 이용하여 유전자 중복에 의해 발생하는 질환을 치료 또는 개선하는 방법에 관한 것이다.

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